

## Supporting Information

### Morphology and Interfacial Design of SnO<sub>2</sub> Thin-Film Anodes for High-Performance Lithium-Ion Batteries

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Parameter	Condition
Target	Sn metallic (99.994-99.999% pure)
Substrate	Stainless steel (~10 nm Ti-coated)
RF Power	60 W (~2.96 W/cm <sup>2</sup> )
Sputtering gas	Ar (15 sccm) O <sub>2</sub> (15 sccm)
Thin film thickness	300-500 nm
Sputtering pressure	2 × 10 <sup>-6</sup> (torr)
Deposition temperature	RT 300°C

**Table TS1.** RF magnetron sputtering conditions of SnO<sub>2</sub> thin films

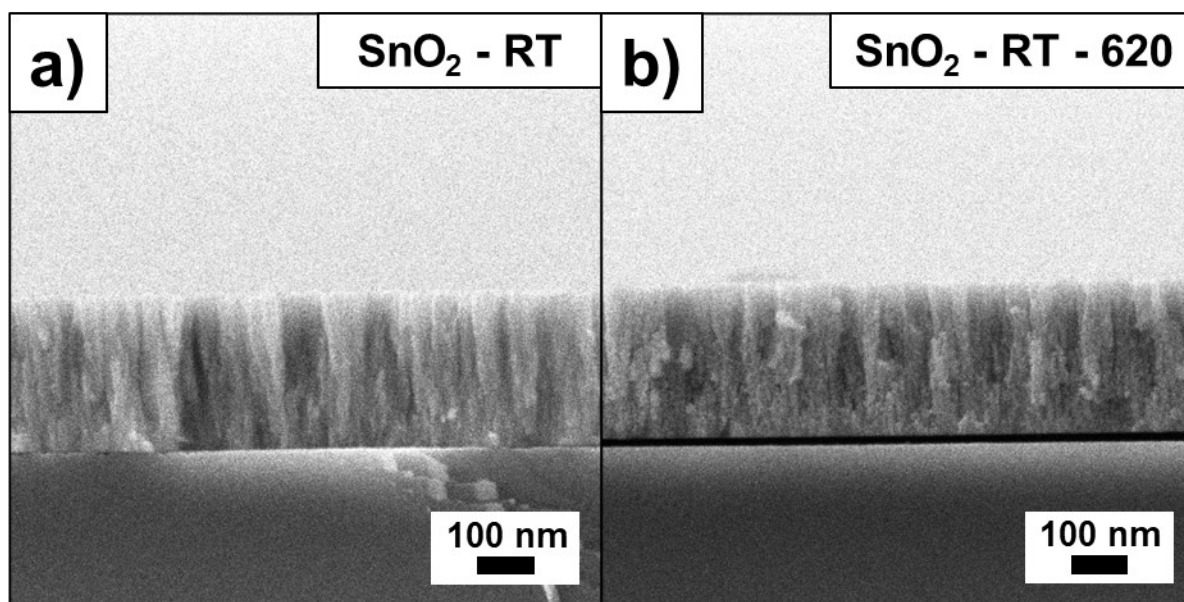
**Table TS2.** Synthesis details of sputtered and annealed SnO<sub>2</sub> electrodes

Sample name	Abbreviation	Annealing temperature	Annealing atmosphere	Deposition temperature
Sputtered SnO <sub>2</sub> electrode at RT	SnO <sub>2</sub> -RT	-	-	RT
Sputtered SnO <sub>2</sub> electrode at 300°C	SnO <sub>2</sub> -300	-	-	300°C
Sputtered SnO <sub>2</sub> electrode at RT - annealed in air	SnO <sub>2</sub> -RT-620	620°C, 2h, 10°C/min	air	RT

Sputtered SnO <sub>2</sub> electrode at 300°C - annealed in air	SnO <sub>2</sub> -300-620			300°C
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**Table TS3.** Modification parameters for SnO<sub>2</sub>-RT-620 electrodes

Sample name	Abbreviation	Coating	Used Electrolyte
Sputtered SnO <sub>2</sub> electrode at RT (Previously SnO <sub>2</sub> -RT-620)	SnO <sub>2</sub> -bare	-	1M LiPF <sub>6</sub> in (EC:DEC:EMC 1:1:1)
Sputtered SnO <sub>2</sub> electrode at RT + C-coated	SnO <sub>2</sub> -C	C	1M LiPF <sub>6</sub> in (EC:DEC:EMC 1:1:1)
Sputtered SnO <sub>2</sub> electrode at RT + C-coated with 5 wt. % VC	SnO <sub>2</sub> -C-VC	C	1M LiPF <sub>6</sub> in (EC:DEC:EMC 1:1:1) + 5 wt. % VC



**Figure FS1.** Cross-sectional SEM images of (a) SnO<sub>2</sub>-RT and (b) SnO<sub>2</sub>-RT-620 thin film electrodes.

A comparative analysis of the XRD patterns (**Figure FS2**) of the bare SnO<sub>2</sub> and C - coated SnO<sub>2</sub> samples demonstrates a complete coincidence of the main peaks at  $2\theta = \sim 26.7^\circ, \sim 33.9^\circ, \sim 37.9^\circ, \sim 51.7^\circ$  and  $\sim 66.2^\circ$ , characteristic of tetragonal rutile SnO<sub>2</sub> (JCPDS card no. 00-041-1445) [19, 21]. Reflections from SS substrate (JCPDS card no. 01-071-4649) are also present. The absence of extraneous phase lines indicates high phase purity, and the identity of the SnO<sub>2</sub> and SnO<sub>2</sub>-C spectra

confirms that the carbon coating does not disturb the  $\text{SnO}_2$  crystal lattice. At the same time, the XRD analysis of  $\text{SnO}_2\text{-C}$  did not reveal characteristic carbon peaks, which is due to its amorphous or nanocrystalline state.

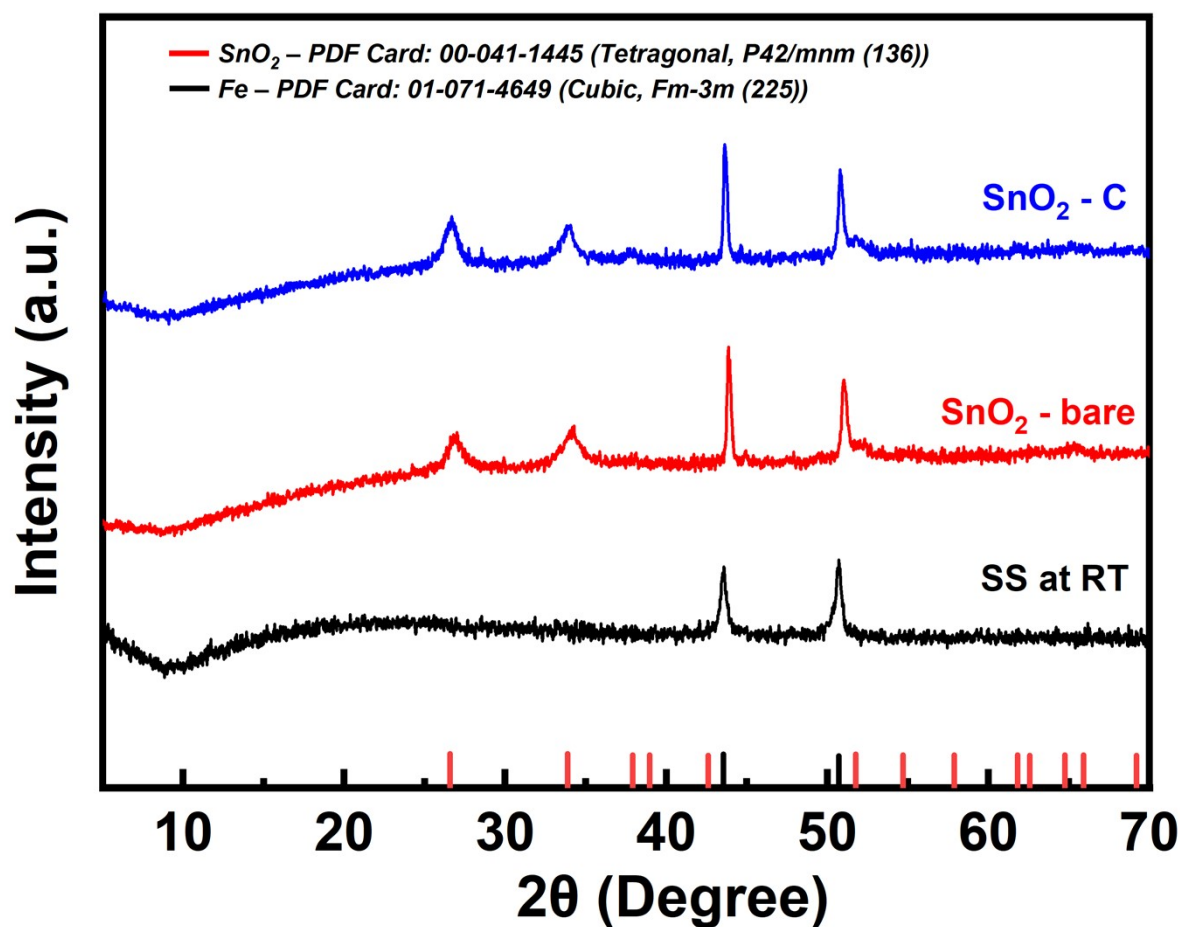


Figure FS2. XRD patterns of  $\text{SnO}_2$ -bare and  $\text{SnO}_2\text{-C}$  thin films.

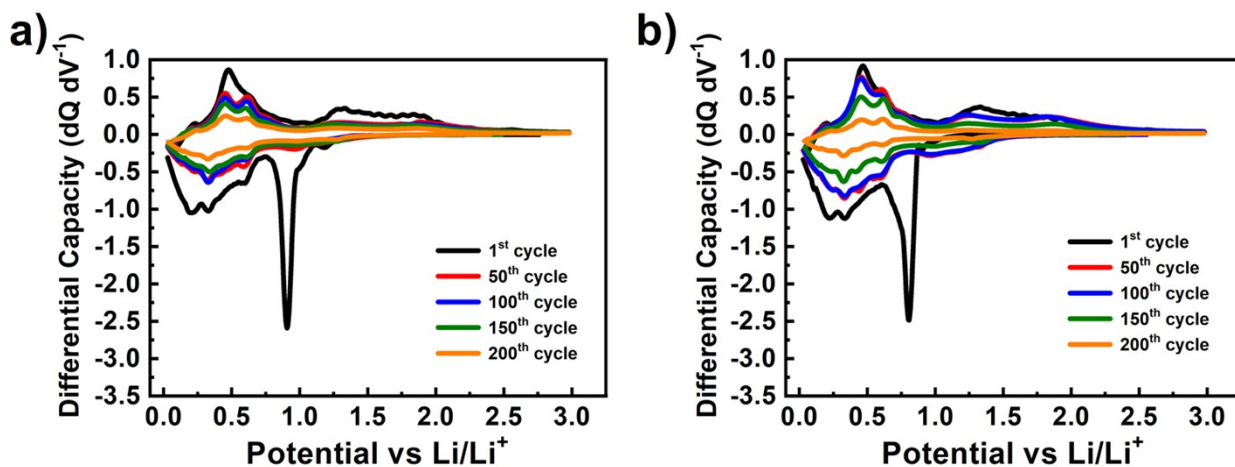


Figure FS3.  $dQ/dV$  curves of  $\text{SnO}_2$ -bare (a) and  $\text{SnO}_2$ -C (b) thin films.

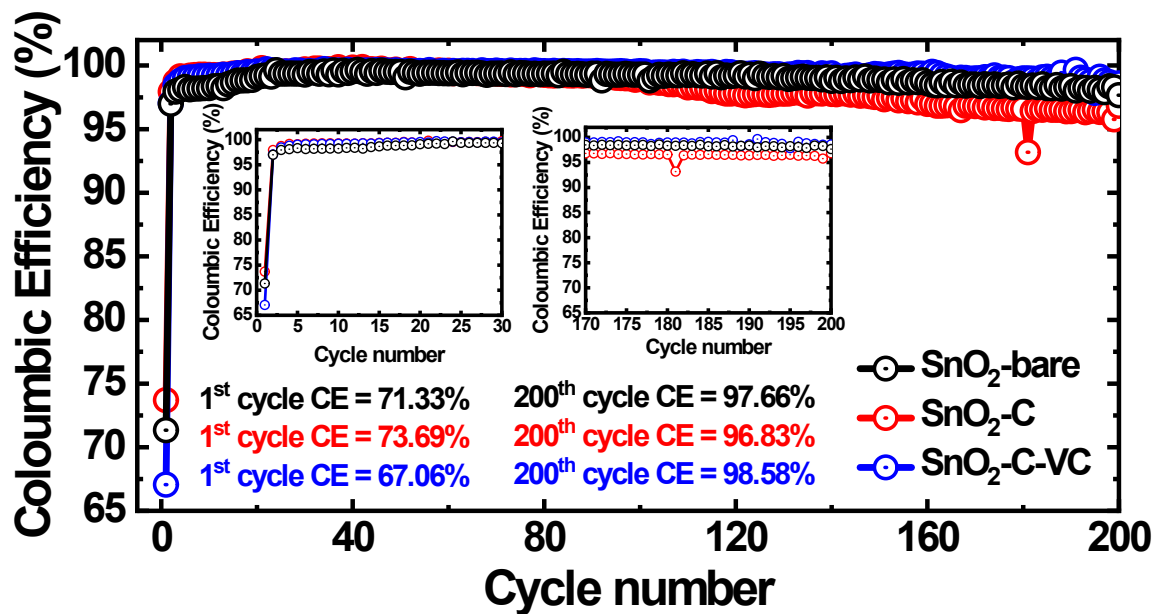


Figure FS4. Coulombic efficiency of  $\text{SnO}_2$ -bare,  $\text{SnO}_2$ -C, and  $\text{SnO}_2$ -C-VC during the initial cycles and after 200 cycles.

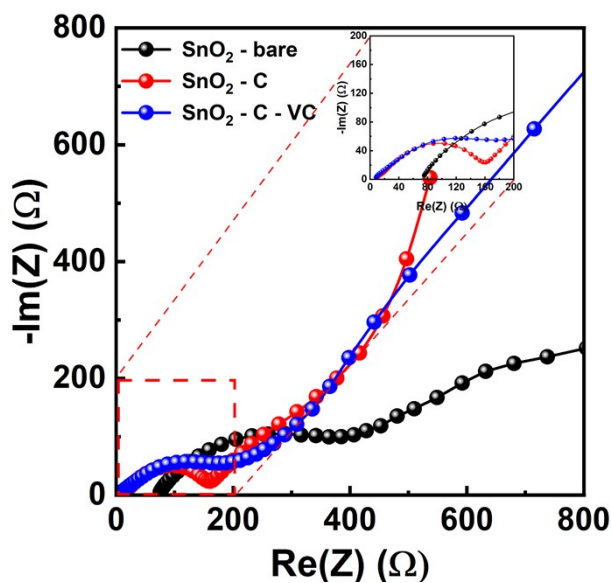


Figure FS5. Nyquist plot of  $\text{SnO}_2$ -bare,  $\text{SnO}_2$ -C and  $\text{SnO}_2$ -C-VC after 200 cycles.